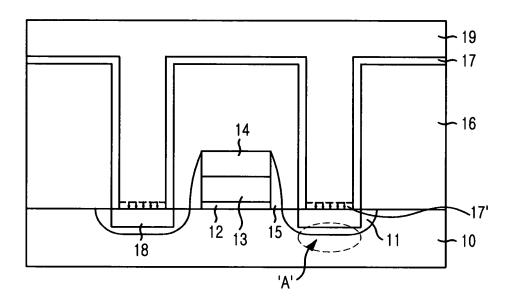
Inventors: In-Haeng Lee et al.
Title: "Method for Forming Metal Silicide
Layer in Active Area of Semiconductor Device"
Sheet 1 of 2

FIG. 1



Inventors: In-Haeng Lee et al. Title: "Method for Forming Metal Silicide Layer in Active Area of Semiconductor Device" Sheet 2 of 2

FIG. 2A

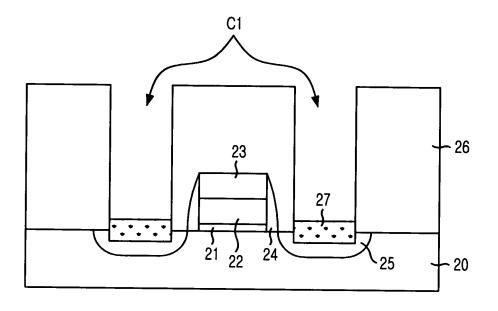


FIG. 2B

